



80236APCW

Customer No. 01333

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Ramanathan Srinivasan, et al

SLURRY FOR CHEMICAL
MECHANICAL POLISHING
SILICON DIOXIDE

Serial No. US 09/526,286

Filed 15 March 2000

Group Art Unit: 1763

Examiner: Goudreau, George A.

I hereby certify that this correspondence is being deposited today with the United States Postal Service as first class mail in an envelope addressed to Commissioner for Patents, Washington, D.C. 20231.

Gina Schmitt
Lois A. Maseer J.M.D. gina schmitt

March 21, 2002

Date

Commissioner for Patents
Washington, D.C. 20231

Sir:

DECLARATION UNDER 37 CFR 1.131

Ramanathan Srinivasan declares that he is a co-inventor, who on March 15, 2000 filed the above-identified application; that he conceived his invention in this country long prior to May 4, 1999 (hereinafter the effective date), the filing date of Kido et. al.; that prior to the effective date he prepared a description of his invention; that he worked substantially continuously with his attorney in preparing the subject application after completion of the enclosed description; that he does not know and does not believe that his invention has been in public prior to his application, and that he has never abandoned the invention.

He further declares that all documents containing evidence of his invention prior to May 4, 1999 are not available. This lack of evidence is primarily due to him leaving Clarkson University for employment during which transition such documents were either mis-placed, lost or destroyed.

He further declares that all statements made herein of his own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Respectfully Submitted,

Ramanathan Srinivasan
Ramanathan Srinivasan

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REGULAR CONTINUATION IN PART FILING

Application Based on

Docket **80236AJDL**

Inventors: Ramanathan Srinivasan, Suryadevara Babu, William G. America and Yie-Shein Her

SLURRY FOR CHEMICAL MECHANICAL POLISHING SILICON DIOXIDE

Assistant Commissioner for Patents,
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Express Mail Label No.: **EL267108852US**

Date: *March 15, 2000*